

**MARKED UP VERSION OF AMENDED CLAIM 1**

**WE CLAIM:**

1. A process for providing lithographic exposures utilizing a line narrowed ~~bas gas~~ discharge laser, comprising the steps of:
  - A. modeling with a computer program lithographic parameters to determine a desired laser spectrum needed to produce a desired lithographic result,
  - B. utilizing a fast responding tuning mechanism to adjust center wavelength of laser pulses in a burst of pulses to achieve an integrated spectrum for the burst of pulses approximating the desired laser spectrum.

**FAX RECEIVED**

**MAR 25 2003**

**TECHNOLOGY CENTER 2800**